

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Kiyoshi Imai

Serial No.: 09/428,052

Filed: October 27, 1999



Group Art Unit: 2815

Examiner: J. Diaz

For: METHOD OF FABRICATING A SEMICONDUCTOR DEVICE CONTAINING NITROGEN IN A GATE OXIDE FILM (AS AMENDED)

PETITION FOR EXTENSION OF TIME

Commissioner for Patents
Washington, D.C. 20231

Date: May 24, 2001

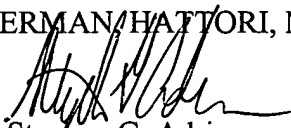
Sir:

Applicant petitions the Commissioner for Patents to extend the time for response to the Office Action dated January 26, 2001, for one month from April 26, 2001, to May 26, 2001.

Attached please find a check in the amount of \$110.00 to cover the cost of the extension. In the event that any additional fees are due in connection with this paper, please charge our Deposit Account No. 01-2340. This paper is filed in triplicate.

Respectfully submitted,

ARMSTRONG, WESTERMAN/HATTORI, McLELAND & NAUGHTON, LLP


Stephen G. Adrian
Reg. No. 32,878

Atty. Docket No. 970901A
1725 K Street, N.W., Suite 1000
Washington, DC 20006
Tel: (202) 659-2930
Fax: (202) 887-0357
SGA/arf

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